

SPUTTERING TARGET, METHOD FOR PRODUCING LAMINATED FILM,  
LAMINATED FILM AND MAGNETIC RECORDING MEDIUM

ABSTRACT

A sputtering target according to the present invention contains Co and one or more metals selected from the group consisting of Cr and Ru, as metal components, wherein a molar ratio of the content of the one or more metals to the content of Co is 1/2 or more, and wherein the sputtering target contains Nb<sub>2</sub>O<sub>5</sub> as a metal oxide component.